

Title (en)

AN ELECTRON BEAM UNIT AND METHOD FOR ADJUSTING ELECTRON BEAMS GENERATED BY AN ELECTRON BEAM UNIT

Title (de)

ELEKTRONENSTRAHLEINHEIT UND VERFAHREN ZUR ANPASSUNG VON DURCH EINE ELEKTRONENSTRAHLEINHEIT ERZEUGTEN ELEKTRONENSTRAHLEN

Title (fr)

UNITÉ À FAISCEAU D'ÉLECTRONS ET PROCÉDÉ POUR AJUSTER DES FAISCEAUX D'ÉLECTRONS GÉNÉRÉS PAR UNE UNITÉ À FAISCEAU D'ÉLECTRONS

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Application

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Priority

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- DE 102008009410 A 20080215

Abstract (en)

[origin: WO2009100877A1] The electron beam unit comprises an electron beam generator (1) for generating an electron beam along an electron beam axis (5), an adjusting and focusing unit (2) for adjusting and focusing the electron beam in a focus plane (6), which adjusting and focusing unit (2) is arranged on the electron beam axis (5) downstream of the electron beam generator (1), and a control (3) for controlling the adjusting and focusing unit (2). The control (3) is adapted to control the adjusting and focusing unit (2) for shifting of the focus plane (6) along the electron beam axis (5) such that the focus plane is shifted back and forth at a predetermined frequency. The orientation of the electron beam axis (5) can be adjusted with the help of the adjusting and focusing unit in such a way that the impact points displayed by the electron beam impact point display unit (4), which is arranged on the electron beam axis (5), form a circular area.

IPC 8 full level

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